

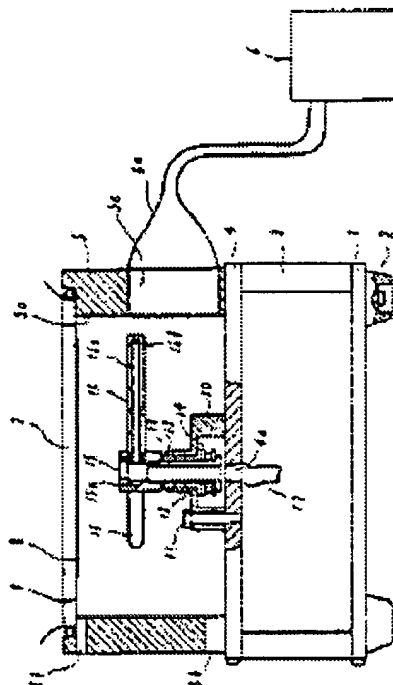
DEVICE FOR CLEANING WAFER WITH AIR

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Abstract of JP1120827

PURPOSE:To collect dust on a wafer easily and maintain environmental cleanliness by a method wherein an air introducing means which introduces compressed air into a nozzle which has a 2nd spouting outlet directed toward one of the circumference directions of a horizontal rotation, a dust collector whose suction side is connected to an exhaust outlet and a wafer holding means which holds a wafer face-down are provided.

CONSTITUTION:If air is introduced into a hollow shaft 13 through a pipe 17, the air is spouted out upward from spouting outlets 15a and 16a from the inside of a sprinkler head 15 through the inside of a nozzle 16 and made to blow against a wafer 8 which is held face-down by a wafer holding means 7. The air is also spouted out from a spouting outlet 16b and, by the reaction caused by the spouting, the nozzle 16 itself is rotated with the sprinkler head 15 and the hollow shaft 13. Therefore, the air is made to blow against the whole surface of the wafer 8 and dust can be securely eliminated. Moreover, by driving a dust collector 6, the air inside is exhausted from an exhaust outlet 5c while the external air is introduced from a suction inlet 5b. At that time, the dust is also discharged from the exhaust outlet.



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